L Number	Hits	Search Text	DB	Time stamp
6	9		USPAT;	2004/02/18 14:42
		("6291130") or ("5856561")).PN.	US-PGPUB; EPO; JPO;	2501/02/10 14.42
<u>.</u>	1	("20020150834").PN.	DERWENT USPAT; US-PGPUB;	2003/06/10 15:25
-	3086104	resin binder polymer resist photoresist	EPO; JPO; DERWENT USPAT;	2003/06/10 15:25
			US-PGPUB; EPO; JPO; DERWENT	2003/00/10 13.23
-	15856	(photoacid acid (photo adj acid)) near generat\$3	USPAT; US-PGPUB; EPO; JPO;	2003/06/10 15:26
-	2055	acetal near moiety) (acetal near compound	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 08:53
-	197	and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 10:41
-	275472	acrylate methacrylate cycloolefin	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:31
-	24	(2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:33
-	16008	gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:16
-	146	<pre>(acrylate methacrylate cycloolefin) and ((resin binder polymer resist photoresist) and ((photoacid acid (photo adj acid)) near generat\$3) and (acetal near moiety) (acetal near compound))</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/10 15:34
-	24	(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/02/09 11:15
-	24	(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:10
	24	((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:29
	14	(((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate) (((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate) ((\$3-methyladamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:27

•				
-	4	((((2-methyladamantyl adj methacrylate)	USPAT;	2003/06/10 15:43
		(2-methyl adj adamantyl adj methacrylate))	US-PGPUB;	
		(((2-methyladamantyl adj methacrylate)	EPO; JPO;	
		(2-methyl adj adamantyl adj methacrylate))	DERWENT	
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate))		
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone "gamma"-butyrolactone)) and		
-		((acrylate methacrylate cycloolefin) and		
1		((resin binder polymer resist photoresist)		
		and ((photoacid acid (photo adj acid)) near		
		generat\$3) and (acetal near moiety) (acetal		
		near compound)))		
_	4	I	USPAT;	2003/06/10 15:43
		(2-methyl adj adamantyl adj methacrylate))	US-PGPUB;	2003/00/10 13.43
		(((2-methyladamantyl adj methacrylate)	EPO; JPO;	
		(2-methyl adj adamantyl adj methacrylate))	DERWENT	
		((\$3-methyladamantyl adj methacrylate)	DERWEIT	
		(\$3-methyl adj adamantyl adj methacrylate))		
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
))) and (gamma-butyrolactone \$6butyrolactone	İ	
		butyrolactone "gamma"-butyrolactone)) and		
		((resin binder polymer resist photoresist)		
		and ((photoacid acid (photo adj acid)) near		
		generat\$3) and (acetal near moiety) (acetal		
		near compound))		
-	4	(((((2-methyladamantyl adj methacrylate)	USPAT;	2004/02/09 11:15
		(2-methyl adj adamantyl adj methacrylate))	US-PGPUB;	
		(((2-methyladamantyl adj methacrylate)	EPO; JPO;	
		(2-methyl adj adamantyl adj methacrylate))	DERWENT	
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate))		
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
))) and (gamma-butyrolactone \$6butyrolactone	i	
		butyrolactone "gamma"-butyrolactone)) and		
		((acrylate methacrylate cycloolefin) and ((resin binder polymer resist photoresist)		
		and ((photoacid acid (photo adj acid)) near		
1		generat\$3) and (acetal near moiety) (acetal		
1		near compound)))) (((((2-methyladamantyl adj		
		methacrylate) (2-methyl adj adamantyl adj		
		methacrylate)) (((2-methyladamantyl adj		
		methacrylate) (2-methyl adj adamantyl adj		
		methacrylate)) ((\$3-methyladamantyladj		
		methacrylate) (\$3-methyl adj adamantyl adj		
		methacrylate)) ((\$3-methyladamantyl adj		
		methacrylate) (\$3-methyl adj adamantyl adj		
		methacrylate)))) and (gamma-butyrolactone		
		\$6butyrolactone butyrolactone		
		"gamma"-butyrolactone)) and ((resin binder		
		polymer resist photoresist) and ((photoacid		
		acid (photo adj acid)) near generat\$3) and		
		(acetal near moiety) (acetal near		
		compound)))		
-	20	(("2003082926") or ("2002150834") or	USPAT;	2003/06/10 16:22
I	1 1	("2002081523") or ("6548221") or	US-PGPUB;	
) 1			
		("2000482359") or ("2002051933") or	EPO; JPO;	
		("2000482359") or ("2002051933") or ("6492091") or ("2002102491") or ("6383713") or ("6348297") or ("6239231")).PN.		

-	24	((("2003082926") or ("2002150834") or	USPAT;	2003/06/10 16:23
		("2002081523") or ("6548221") or ("2000482359") or ("2002051933") or	US-PGPUB;	
		("6492091") or ("2002102491") or ("6383713")	EPO; JPO; DERWENT	
		or ("6348297") or ("6239231")).PN.)	Distributi	·
		((((((2-methyladamantyl adj methacrylate)		
		(2-methyl adj adamantyl adj methacrylate))		
		(((2-methyladamantyl adj methacrylate)		
		(2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
		((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
))) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone "gamma"-butyrolactone)) and		
		((acrylate methacrylate cycloolefin) and ((resin binder polymer resist photoresist)		
		and ((photoacid acid (photo adj acid)) near		
		generat\$3) and (acetal near moiety) (acetal		
		near compound)))) (((((2-methyladamantyl adj		
ļ		methacrylate) (2-methyl adj adamantyl adj		
		methacrylate)) (((2-methyladamantyl adj		
		methacrylate) (2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj		
		methacrylate) (\$3-methyl adj adamantyl adj		
		methacrylate)) ((\$3-methyladamantyl adj		
		methacrylate) (\$3-methyl adj adamantyl adj		
		methacrylate)))) and (gamma-butyrolactone		
		\$6butyrolactone butyrolactone "gamma"-butyrolactone)) and ((resin binder		
		polymer resist photoresist) and ((photoacid		
		acid (photo adj acid)) near generat\$3) and		
		(acetal near moiety) (acetal near		
	2055	compound))))		
	2055	acetal near moiety) (acetal near compound	USPAT:	2003/06/11 09:05
			US-PGPUB; EPO; JPO;	
	•		DERWENT	
-	2055	acetal near moiety) (acetal near compound	USPAT;	2003/06/11 09:37
			US-PGPUB;	
			EPO; JPO;	
	1377	YAMAMOTO-HAJIME	DERWENT USPAT;	2004/02/16 17:56
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	2004/02/10 17.30
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO; JPO;	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT	
]	MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI		
	1	TAKECHI-SATOSHI-C-O-FUJITSU-LI		
-	2	(YAMAMOTO-HAJIME	USPAT;	2003/06/11 10:03
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	, == ==
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO; JPO;	
1		YAMAMOTO-HAJIMU MURAKAMI-KENICHI MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	DERWENT	
1		MORAKAMI-KENICHIROU TAKECHI-SATOSHI		
		TAKECHI-SATOSHI-C-O-FUJITSU-LI) and (acetal		
		near moiety) (acetal near compound)		
-	0	20020150834.URPN.	USPAT	2003/06/11 10:03
_	44	(YAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU	USPAT;	2003/06/11 11:19
1		YAMAMOTO-HAJIME-C-O-CANON-KABU YAMAMOTO-HAJIME-C-O-CANON-K-K	US-PGPUB; EPO; JPO;	
	·	YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	1	
		TAKECHI-SATOSHI		
		TAKECHI-SATOSHI-C-O-FUJITSU-LI) and		
		(photoresist resist) and (\$5acid near generat\$3)		
_	6	3	USPAT;	2003/06/11 10:04
		US-6548221-\$).did. or (US-20020150834-\$ or	US-PGPUB;	2000,00722 10.04
		US-20030044718-\$).did. or	JPO	
		(JP-2002311587-\$).did.		

-	43	((yAMAMOTO-HAJIME YAMAMOTO-HAJIME-C-O-CANON-KABU	USPAT;	2003/06/11 10:09
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	EPO; JPO; DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	DEKMENT	
		TAKECHI-SATOSHI		
		TAKECHI-SATOSHI-C-O-FUJITSU-LI) and		
		(photoresist resist) and (\$5acid near		
		generat\$3)) not ((US-6517991-\$ or		
ļ		US-6291130-\$ or US-6548221-\$).did. or		
		(US-20020150834-\$ or US-20030044718-\$).did.		1
		or (JP-2002311587-\$).did.)		
-	18633	' = = ' (wedness) (and so tack of all	USPAT;	2003/06/11 10:43
		inhibitor) compound)	US-PGPUB;	
			EPO; JPO;	
_	5	((acetal) same (additive (dissolution adj	DERWENT	5000/06/01 10 16
		inhibitor) compound)) and	USPAT;	2003/06/11 10:46
		(((yAMAMOTO-HAJIME	US-PGPUB; EPO; JPO;	
		YAMAMOTO-HAJIME-C-O-CANON-KABU	DERWENT	
		YAMAMOTO-HAJIME-C-O-CANON-K-K	BERNEIT	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI		
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU		
	1	TAKECHI-SATOSHI	1	
		TAKECHI-SATOSHI-C-O-FUJITSU-LI) and	İ	
		(photoresist resist) and (\$5acid near		
		generat\$3)) not ((US-6517991-\$ or		
		US-6291130-\$ or US-6548221-\$).did. or		
		(US-20020150834-\$ or US-20030044718-\$).did. or (JP-2002311587-\$).did.))		
	1477	lactone same acetal	USPAT;	2002/06/11 10 40
		awoodio bame accear	US-PGPUB;	2003/06/11 10:48
			EPO; JPO;	
1			DERWENT	
-	444	((acetal) same (additive (dissolution adj	USPAT;	2003/06/11 12:35
		inhibitor) compound)) and (photoresist	US-PGPUB;	,,
		resist) and (\$5acid near generat\$3)	EPO; JPO;	
			DERWENT	
-		di-t-butoxyacetyl adj bisphenol adj "A"	USPAT;	2003/06/11 12:36
			US-PGPUB;	
			EPO; JPO;	
-	5140	(acid adj (labile cleavable cleve	DERWENT USPAT:	2003/06/11 15:09
		dissociable)) (acid near elminat\$4)	US-PGPUB;	2003/06/11 15:09
		The state of the s	EPO; JPO;	
			DERWENT	
-	141586	acetal ketal (\$5ethoxy\$5ethoxy)	USPAT;	2003/06/11 15:26
		tetrahydrofuranyl tetrahydropyranyl thp thf	US-PGPUB;	
	.	-	EPO; JPO;	
	2.00	//	DERWENT	
1 -	2482	((acid adj (labile cleavable cleve	USPAT;	2003/06/11 15:26
1		dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy)	US-PGPUB;	
		tetrahydrofuranyl tetrahydropyranyl thp thf	EPO; JPO;	
)	DERWENT	
-	564	(((acid adj (labile cleavable cleve	USPAT;	2003/06/11 15:41
	[dissociable)) (acid near elminat\$4)) and	US-PGPUB;	2000,00/11 10:41
	[(acetal ketal (\$5ethoxy\$5ethoxy)	EPO; JPO;	
		tetrahydrofuranyl tetrahydropyranyl thp thf	DERWENT	
)) and (430/270.1.ccls.)		
_	14	(((2-methyladamantyl adj methacrylate)	USPAT;	2003/06/11 15:28
		(2-methyl adj adamantyl adj methacrylate))	US-PGPUB;	
		(((2-methyladamantyl adj methacrylate)	EPO; JPO;	
		(2-methyl adj adamantyl adj methacrylate))	DERWENT	
		((\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate))		
		((\$3-methyladamantyladj methacrylate))	ļ	
		(\$3-methyl adj adamantyl adj methacrylate)		
))) and (gamma-butyrolactone \$6butyrolactone		
·	l	butyrolactone "gamma"-butyrolactone)		

•				
-	7	((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy)	USPAT; US-PGPUB;	2003/06/11 15:29
		tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and	EPO; JPO; DERWENT	
		((((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate))		
		(((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate))		
		((\$3-methyladamantyladj methacrylate) (\$3-methyladamantyladj methacrylate)		
		((\$3-methyladamantyl adj methacrylate) (\$3-methyladamantyl adj methacrylate)		
))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone))		
-	0	20030073030.URPN.	USPAT	2003/06/11 15:30
_	14718	\$5acid near generat\$3	USPAT; US-PGPUB; EPO; JPO;	2003/06/11 15:40
-	485	((((acid adj (labile cleavable cleve	DERWENT USPAT;	2003/06/11 15:40
		dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy)	US-PGPUB; EPO; JPO;	
		tetrahydrofuranyl tetrahydropyranyl the thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)	DERWENT	
-	484790	acrylic acrylate methacrylate methacrylic	USPAT; US-PGPUB; EPO; JPO;	2003/06/11 15:41
-	426	(((((acid adj (labile cleavable cleve	DERWENT USPAT;	2002/06/11 15 41
		dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)	US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:41
	253	"153" and (430/270.1.ccls.)	USPAT; US-PGPUB;	2003/06/11 15:41
			EPO; JPO; DERWENT	
-	426	((((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy)	USPAT; US-PGPUB; EPO; JPO;	2003/06/11 15:44
		tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near	DERWENT	
		generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and		
_	373	(430/270.1.ccls.) ((((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and	USPAT;	2003/06/11 15:48
		(acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf	US-PGPUB; EPO; JPO;	
)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate	DERWENT	
		methacrylate methacrylic)) and		
		(430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)		

·				
	9	dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)) not ((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and ((((2-methyladamantyl adj methacrylate) (2-methyl adj adamantyl adj methacrylate) ((2-methyladamantyl adj methacrylate) ((33-methyladamantyl adj methacrylate) ((\$3-methyladamantyl adj methacrylate) ((\$3-methyladamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone))) ((((((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate methacrylate methacrylic) and ((ceid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition)) not ((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and ((resist binder photoresist resin) near composition) not ((((acid adj (labile cleavable cleve dissociable)) (acid near elminat\$4)) and (acetal ketal (\$5ethoxy\$5ethoxy) tetrahydrofuranyl tetrahydropyranyl thp thf)) and (430/270.1.ccls.)) and (methacrylate) ((2-methyladamantyl adj methacrylate) ((2-methyladamantyl adj methacrylate) ((\$3-methyladamantyl adj methacrylate) ((\$3-methyladamantyl adj methacrylate)	USPAT; US-PGPUB; EPO; JPO; DERWENT US-PGPUB; EPO; JPO; DERWENT	2003/06/11 15:48
		(\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate) (\$3-methyladamantyl adj methacrylate) (\$3-methyl adj adamantyl adj methacrylate)))) and (gamma-butyrolactone \$6butyrolactone butyrolactone "gamma"-butyrolactone)))) and "drrl"		

<u> </u>	_			
-	133		USPAT;	2003/06/11 17:30
		dissociable)) (acid near elminat\$4)) and	US-PGPUB;	2003/00/11 17:30
		(acetal ketal (\$5ethoxy\$5ethoxy)	EPO; JPO;	
		tetrahydrofuranyl tetrahydropyranyl thp thf	DERWENT	
)) and (430/270.1.ccls.)) and (\$5acid near generat\$3)) and (acrylic acrylate		
		methacrylate methacrylic)) and		
		(430/270.1.ccls.)) and ((resist binder		
		photoresist resin) near composition)) not		
	ĺ	(((((acid adj (labile cleavable cleve		
		dissociable)) (acid near elminat\$4)) and		
		(acetal ketal (\$5ethoxy\$5ethoxy)		
		tetrahydrofuranyl tetrahydropyranyl tho thf		
1)) and (430/270.1.ccls.)) and		1
		((((2-methyladamantyl adj methacrylate)		
i		(2-methyl adj adamantyl adj methacrylate))	Ì	ĺ
		(((2-methyladamantyl adj methacrylate)		
		(2-methyl adj adamantyl adj methacrylate)) ((\$3-methyladamantyl adj methacrylate)		
		(\$3-methyl adj adamantyl adj methacrylate)		
		((\$3-methyladamantyl adj methacrylate))		
		(\$3-methyl adj adamantyl adj methacrylate)		
		())) and (gamma-butyrolactone \$6butyrolactone		
		butyrolactone "gamma"-butyrolactone))))		
		and (dissolution add inhibitor)		
-	8819	gamma-butyrolactone	USPAT;	2003/06/12 11:50
			US-PGPUB;	. , == =======
-			EPO; JPO;	1
_	373305	nattornéa como (undo-la du)	DERWENT	
	373303	<pre>pattern\$3 same (underlying) same (resist photoresist) saem (mask)</pre>	USPAT;	2003/06/12 13:34
		procedure / Saem (mask)	US-PGPUB;	
	İ		EPO; JPO; DERWENT	
-	44827	(pattern\$3 same (underlying) same (resist	USPAT;	2003/06/12 13:36
		photoresist) saem (mask)) same	US-PGPUB;	2003/06/12 13:36
-		(conventional well-known well adj known)	EPO; JPO;	
			DERWENT	
-	504	1 'TENDED DOME (GENTLE TATED) Balle (FERTSE	USPAT;	2003/06/12 13:36
		photoresist) saem (mask)) same	US-PGPUB;	, , , , , , , , , , , , , , , , , , , ,
ļ	•	(conventional well-known well adj known)) and (430/270.1.ccls.)	EPO; JPO;	1.
_	374		DERWENT	
		photoresist) saem (mask)) same	USPAT;	2003/06/12 13:43
		(conventional well-known well adj known))	US-PGPUB;	
		and (430/270.1.ccls.)) and (semiconductor	EPO; JPO; DERWENT	
		semi-conductor VLSI LSI micropatterning	DERWINI	
		mircorfabrication)		
] -	276		USPAT	2003/06/12 13:43
1		photoresist) saem (mask)) same		,
		(conventional well-known well adj known))		
1		and (430/270.1.ccls.)) and (semiconductor		
		semi-conductor VLSI LSI micropatterning mircorfabrication)		
-	1	("6673511").PN.	ITODA W	0001/05/55
	_		USPAT;	2004/02/09 10:47
	i		US-PGPUB; EPO; JPO;	
			DERWENT	
-	5	(("20030232273") or ("6369181") or	USPAT;	2004/02/09 11:09
		("6013411")).PN.	US-PGPUB;	
]			EPO; JPO;	
_	37	(C) mother lader and 2	DERWENT	
	3/	(\$3-methyladamantyl adj methacrylate)	USPAT;	2004/02/09 11:15
		(\$3-methyl adj adamantyl adj methacrylate)	US-PGPUB;	
			EPO; JPO;	
-	17746	gamma-butyrolactone \$6butyrolactone	DERWENT	2004/02/22
		butyrolactone "gamma"-butyrolactone	USPAT; US-PGPUB;	2004/02/09 11:16
		- James Audionic	EPO; JPO;	
			DERWENT	•

				
-	23	1 () The mostly industry in day mountable viace)	USPAT;	2004/02/09 11:16
		(\$3-methyl adj adamantyl adj methacrylate)	US-PGPUB;	
) and (gamma-butyrolactone \$6butyrolactone	EPO; JPO:	
		butyrolactone "gamma"-butyrolactone)	DERWENT	
-	6		USPAT;	2004/02/09 11:17
		(\$3-methyl adj adamantyl adj methacrylate)	US-PGPUB:	,,
) same (gamma-butyrolactone \$6butyrolactone	EPO; JPO;	
		butyrolactone "gamma"-butyrolactone)	DERWENT	
.=	1	("6673511").PN.	USPAT:	2004/02/16 14:00
			US-PGPUB;	2004/02/10 14:00
			EPO; JPO;	
			DERWENT	
-	1674	acetal same lactone	USPAT;	2004/02/16 13:30
			US-PGPUB;	2004/02/16 13:30
			EPO; JPO; DERWENT	
-	88	acetal same gamma-butyrolactone	1	0001/00/100
		January 20140 Colle	USPAT;	2004/02/16 13:48
	İ		US-PGPUB;	
			EPO; JPO;	
_	5	(("4996121") or ("6495310") or ("6387595")	DERWENT	
1		or ("6541183") or ("6660445")).PN.	USPAT	2004/02/16 13:51
_	362	OF (0341103") OF ("6660445")).PN.		
	362	benzyl same (acid adj labile)	USPAT;	2004/02/16 14:01
			US-PGPUB;	
			EPO; JPO;	
		(#6200 #42 #1)	DERWENT	
-	1	("6383713").PN.	USPAT	2004/02/16 17:36
-	246	(acetal adj moiety)	USPAT;	2004/02/16 17:37
	}		US-PGPUB;	, ,
			EPO; JPO;	
		i .	DERWENT	
-	159212	acid near5 (eliminat\$3 remov\$3 labile	USPAT;	2004/02/16 17:38
		cleav\$5)	US-PGPUB;	2001/01/10 17:30
			EPO; JPO;	
			DERWENT	
-	17	((acetal adj moiety)) same (acid near5	USPAT;	2004/02/16 17:39
	•	(eliminat\$3 remov\$3 labile cleav\$5))	US-PGPUB;	2004/02/16 17:39
		, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT	
-	0	20020150834.URPN.	USPAT	2004/02/16 17:47
1 -	1460	yAMAMOTO-HAJIME	USPAT;	2004/02/16 17:47
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	2004/02/16 17:56
		YAMAMOTO-HAJIME-C-O-CANON-K-K		
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	EPO; JPO; DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU	DEKMENT	Į
		TAKECHI-SATOSHI		<u> </u>
		TAKECHI-SATOSHI-C-O-FUJITSU-LI	i	
_	147	(YAMAMOTO-HAJIME	HODAM	2004/00/55 == =
		YAMAMOTO-HAJIME-C-O-CANON-KABU	USPAT;	2004/02/16 17:57
		YAMAMOTO-HAJIME-C-O-CANON-K-K	US-PGPUB;	
		YAMAMOTO-HAJIMU MURAKAMI-KENICHI	EPO; JPO;	
1		MIRAKAMI - KENI CHIDO MIDAKAMI KENI CHI	DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU TAKECHI-SATOSHI		
]		TAKEOUT CAMOCUT C O DUTTEMOT '		
	1	TAKECHI-SATOSHI-C-O-FUJITSU-LI) AND (RESIST		
	20	PHOTORESIST)		
	20	((YAMAMOTO-HAJIME	USPAT;	2004/02/16 17:57
		YAMAMOTO-HAJIME-C-O-CANON-KABU	US-PGPUB;	
		YAMAMOTO-HAJIME-C-O-CANON-K-K	EPO; JPO;	
	1	YAMAMOTO-HAJIMU MURAKAMI-KENICHI	DERWENT	
		MURAKAMI-KENICHIRO MURAKAMI-KENICHIROU]	
		TAKECHI-SATOSHI		
]	TAKECHI-SATOSHI-C-O-FUJITSU-LI) AND (RESIST		
		PHOTORESIST)) AND ((ACID PHOTOACID) NEAR		
	<u> </u>	GENERATOR)		

```
=> s 14
L5
```

0 L4

FILE 'HCAPLUS' ENTERED AT 13:40:50 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 13:40:50 ON 16 FEB 2004 CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'CAPLUS' ENTERED AT 13:40:50 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FULL ESTIMATED COST

SINCE FILE TOTAL ENTRY SESSION 0.42 0.63

0 ANSWERS

=> FIL CAPLUS, USPATFULL, HCAPLUS COST IN U.S. DOLLARS

0 TO 0 SEA SSS SAM L2 AND L1

PROJECTED ITERATIONS: PROJECTED ANSWERS:

BATCH **COMPLETE** 0 TO

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

100.0% PROCESSED SEARCH TIME: 00.00.01

0 ITERATIONS

SAMPLE SEARCH INITIATED 13:40:45 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED -

=> s 13 sss sam

Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L2 AND L1

G1

L3 HAS NO ANSWERS Ll SCR 2067 L2 STR

=> d

L3 QUE L2 AND L1

=> que L2 AND L1

STRUCTURE UPLOADED

Uploading C:\Program Files\Stnexp\Queries\09940665-2.str

L1 SCREEN CREATED

=> screen 2067

ENTER SCREEN EXPRESSION OR (END):end

=> file reg COST IN U.S. DOLLARS

SINCE FILE ENTRY

4.15

TOTAL SESSION 4.78

FULL ESTIMATED COST

FILE 'REGISTRY' ENTERED AT 13:41:10 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9 DICTIONARY FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at: http://www.cas.org/ONLINE/DBSS/registryss.html

=> Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END):end

=> screen 2067

L6 SCREEN CREATED

Uploading C:\Program Files\Stnexp\Queries\09940665-3.str

L7 STRUCTURE UPLOADED

=> que L7 AND L6

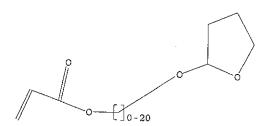
L8QUE L7 AND L6

=> d

L8 HAS NO ANSWERS

1.6 SCR 2067

L7 STR



G1

Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L7 AND L6

=> s 18 sss sam

SAMPLE SEARCH INITIATED 13:42:51 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED -20 TO ITERATE

100.0% PROCESSED SEARCH TIME: 00.00.01

20 ITERATIONS

1 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH

COMPLETE

PROJECTED ITERATIONS:

132 TO 1 TO

668

PROJECTED ANSWERS:

```
=> FIL CAPLUS, USPATFULL, HCAPLUS
COST IN U.S. DOLLARS
```

SINCE FILE ENTRY

SESSION 1.26

TOTAL

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 13:42:57 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 13:42:57 ON 16 FEB 2004 CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'HCAPLUS' ENTERED AT 13:42:57 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s 19

L10

5 L9

=> duplicates remove 110 DUPLICATE PREFERENCE IS 'CAPLUS, USPATFULL, HCAPLUS' KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n PROCESSING COMPLETED FOR L10 L113 DUPLICATE REMOVE L10 (2 DUPLICATES REMOVED)

=> d l11 1-3 ibib hitstr

L11 ANSWER 1 OF 3 USPATFULL on STN

ACCESSION NUMBER:

91:17029 USPATFULL

TITLE:

Electrophotographic lithographic printing plate

precursor containing resin having hydroxy group forming

functional group

INVENTOR(S):

Kato, Eiichi, Shizuoka, Japan Ishii, Kazuo, Shizuoka, Japan

PATENT ASSIGNEE(S):

Fuji Photo Film Co., Ltd., Kanagawa, Japan (non-U.S.

corporation)

NUMBER KIND DATE ------- -----

PATENT INFORMATION:

US 4996121 19910226

APPLICATION INFO.:

US 1989-293400 19890104 (7)

> NUMBER DATE

PRIORITY INFORMATION:

JP 1988-265 19880106 19880127

DOCUMENT TYPE:

JP 1988-14577 Utility

FILE SEGMENT:

Granted

PRIMARY EXAMINER:

McCamish, Marion C.

ASSISTANT EXAMINER: LEGAL REPRESENTATIVE:

RoDee, Christopher D. Sughrue, Mion, Zinn, Macpeak & Seas

NUMBER OF CLAIMS:

10

EXEMPLARY CLAIM:

1

LINE COUNT:

1200

CAS INDEXING IS AVAILABLE FOR THIS PATENT.

IT 124660-88-4

(electrophotog. plate with photoconductive layer containing, for lithog. plate fabrication)

RN 124660-88-4 USPATFULL

CN

2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl 2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl

2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM 1

CRN 121462-74-6 CMF C10 H16 O4

CRN 997-46-6 CMF C8 H14 O3

$$^{\rm O}_{\rm HO^-}$$
 (CH₂) $_{\rm 4^{-}O^{-}C^{-}C^{-}Me}$

CM3

CRN 97-63-2 CMF C6 H10 O2

L11 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1

ACCESSION NUMBER:

1990:468420 CAPLUS

DOCUMENT NUMBER:

113:68420

TITLE:

Direct-imaging lithographic original plate having image-receiving layer with binder containing protected hydroxy-substituted polymer and hardener

INVENTOR(S):

PATENT ASSIGNEE(S):

Kato, Eiichi; Ishii, Kazuo Fuji Photo Film Co., Ltd., Japan Jpn. Kokai Tokkyo Koho, 13 pp.

SOURCE:

CODEN: JKXXAF

DOCUMENT TYPE:

Patent

LANGUAGE:

Japanese

FAMILY ACC. NUM. COUNT:

PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE --------------------JP 01271292 A2 19891030 JP 1988-100192 19880425 PRIORITY APPLN. INFO.: JP 1988-100192

124660-88-4

RL: USES (Uses)

(binder, for image-receiving layer, for direct-imaging lithog. plate, hydrophilicity associated with oil-based ink affinity in)

124660-88-4 CAPLUS

2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl 2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM

CRN 121462-74-6 CMF C10 H16 O4

CM

CRN 997-46-6 CMF C8 H14 O3

CM 3

CRN 97-63-2 CMF C6 H10 O2

L11 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2 ACCESSION NUMBER:

1990:601290 CAPLUS DOCUMENT NUMBER:

113:201290

TITLE: Electrophotographic lithographic printing plate

precursor

INVENTOR (S): Kato, Eiichi; Ishii, Kazuo PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan Eur. Pat. Appl., 43 pp. SOURCE:

CODEN: EPXXDW

DOCUMENT TYPE:

Patent English

LANGUAGE: FAMILY ACC. NUM. COUNT:

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 323854 EP 323854 R: DE, GB	A2 A3	19890712 19910703	EP 1989-100179	19890105
JP 01179052 JP 01191158 US 4996121 PRIORITY APPLN. INFO.	A2 A2 A	19890717 19890801 19910226	JP 1988-265 JP 1988-14577 US 1989-293400 JP 1988-265 JP 1988-14577	19880106 19880127 19890104 19880106 19880127

124660-88-4

RL: USES (Uses)

(electrophotog. plate with photoconductive layer containing, for lithog. plate fabrication)

124660-88-4 CAPLUS RN

2-Propenoic acid, 2-methyl-, ethyl ester, polymer with 4-hydroxybutyl

2-methyl-2-propenoate and 2-[(tetrahydro-2-furanyl)oxy]ethyl 2-methyl-2-propenoate (9CI) (CA INDEX NAME)

CM

CRN 121462-74-6 CMF C10 H16 O4

CM2

CRN 997-46-6 CMF C8 H14 O3

CM 3

CRN 97-63-2 CMF C6 H10 O2

=>

FILE 'REGISTRY' ENTERED AT 13:43:52 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 American Chemical Society (ACS)

Property values tagged with IC are from the ${\tt ZIC/VINITI}$ data file provided by ${\tt InfoChem.}$

STRUCTURE FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9 DICTIONARY FILE UPDATES: 15 FEB 2004 HIGHEST RN 650577-28-9

TSCA INFORMATION NOW CURRENT THROUGH JULY 14, 2003

Please note that search-term pricing does apply when conducting SmartSELECT searches.

Crossover limits have been increased. See HELP CROSSOVER for details.

Experimental and calculated property data are now available. For more information enter HELP PROP at an arrow prompt in the file or refer to the file summary sheet on the web at: http://www.cas.org/ONLINE/DBSS/registryss.html

=>Testing the current file.... screen

ENTER SCREEN EXPRESSION OR (END): end

=> screen 2067

L12 SCREEN CREATED

Uploading C:\Program Files\Stnexp\Queries\09940665-4.str

L13 STRUCTURE UPLOADED

=> que L13 AND L12

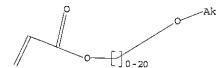
L14 QUE L13 AND L12

=> d

L14 HAS NO ANSWERS

L12

SCR 2067



Gl

Structure attributes must be viewed using STN Express query preparation. L14 QUE ABB=ON PLU=ON L13 AND L12

=> s 114 sss sam SAMPLE SEARCH INITIATED 13:44:44 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED - 8008 TO ITERATE

12.5% PROCESSED 1000 ITERATIONS INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED) SEARCH TIME: 00.00.01

50 ANSWERS

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 154798 TO 1655

PROJECTED ANSWERS:

154798 TO 165522 64257 TO 71237

L15 50 SEA SSS SAM L13 AND L12

=>Testing the current file.... screen

scree

ENTER SCREEN EXPRESSION OR (END):end

```
L16
      SCREEN CREATED
```

Uploading C:\Program Files\Stnexp\Queries\09940665-5.str

STRUCTURE UPLOADED

=> que L17 AND L16

L18 QUE L17 AND L16

=> d

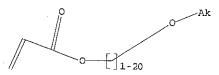
L18 HAS NO ANSWERS

L16

SCR 2067

L17

STR



G1

Structure attributes must be viewed using STN Express query preparation. QUE ABB=ON PLU=ON L17 AND L16

=> s 118 sss sam

SAMPLE SEARCH INITIATED 13:45:58 FILE 'REGISTRY' SAMPLE SCREEN SEARCH COMPLETED -8719 TO ITERATE

11.5% PROCESSED

1000 ITERATIONS

INCOMPLETE SEARCH (SYSTEM LIMIT EXCEEDED)

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

COMPLETE BATCH

PROJECTED ITERATIONS:

168786 TO

PROJECTED ANSWERS:

179974 62982 TO 69894

50 SEA SSS SAM L17 AND L16

=> FIL CAPLUS, USPATFULL, HCAPLUS

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

50 ANSWERS

FULL ESTIMATED COST

ENTRY 1.68

SESSION 22.86

FILE 'CAPLUS' ENTERED AT 13:46:03 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 13:46:03 ON 16 FEB 2004

CA INDEXING COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'HCAPLUS' ENTERED AT 13:46:03 ON 16 FEB 2004 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2004 AMERICAN CHEMICAL SOCIETY (ACS)

=> s l19

L20 106 L19

=> s 120 and (resist or photoresist)

5 L20 AND (RESIST OR PHOTORESIST)

=> duplicates remove 121

DUPLICATE PREFERENCE IS 'CAPLUS, USPATFULL, HCAPLUS'

KEEP DUPLICATES FROM MORE THAN ONE FILE? Y/(N):n

PROCESSING COMPLETED FOR L21

2 DUPLICATE REMOVE L21 (3 DUPLICATES REMOVED)

=> d 122 1-2 ibib hitstr

L22 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 1

ACCESSION NUMBER: 2002:556013 CAPLUS

DOCUMENT NUMBER: 137:116960

TITLE: Lithographic plate having conformal overcoat and

photosensitive layer on a rough substrate

INVENTOR (S): Teng, Gary Ganghui

PATENT ASSIGNEE(S):

USA

SOURCE:

U.S. Pat. Appl. Publ., 10 pp., Cont.-in-part of U.S. Ser. No. 873,598.

CODEN: USXXCO

DOCUMENT TYPE: LANGUAGE:

Patent English

FAMILY ACC. NUM. COUNT:

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 2002098447 US 6495310	A1 B2	20020725	US 2002-46789	20020115
US 6387595 US 2003036019 US 6541183	B1 A1 B2	20020514 20030220 20030401	US 2000-699784 US 2001-873598	20001030 20010604
PRIORITY APPLN. INFO.		20030401	US 2000-699784 A2	20001030

US 2001-873598 A2 20010604 443150-29-6P, Ebecryl RX 8301-Sartomer SR 399 copolymer

RL: SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(photosensitive layer of lithog. printing plate containing)

RN 443150-29-6 CAPLUS

2-Propenoic acid, 2-[[3-hydroxy-2,2-bis[[(1-oxo-2-

propenyl)oxy]methyl]propoxy]methyl]-2-[[(1-oxo-2-propenyl)oxy]methyl]-1,3propanediyl ester, polymer with Ebecryl RX 8301 (9CI) (CA INDEX NAME)

CM

CRN 344346-13-0 CMF Unspecified CCI PMS, MAN

*** STRUCTURE DIAGRAM IS NOT AVAILABLE ***

CRN 60506-81-2 CMF C25 H32 O12

L22 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2004 ACS on STN DUPLICATE 2

ACCESSION NUMBER:

2002:429450 CAPLUS

DOCUMENT NUMBER:

137:13269

INVENTOR(S):

TITLE:

Photosensitive composition for lithog. printing plate

PATENT ASSIGNEE(S):

Fujita, Kazuo; Tan, Shiro Fuji Photo Film Co., Ltd., Japan

SOURCE:

U.S. Pat. Appl. Publ., 20 pp. CODEN: USXXCO

DOCUMENT TYPE:

Patent LANGUAGE: English

FAMILY ACC. NUM. COUNT:

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATI	ON NO.	DATE
US 2002068235 US 6660445	A1 B2	20020606	US 2001-9	70988	20011005
JP 2002122989 CN 1355448	A2 A	20020426	JP 2000-3 CN 2000-1		20001013
JP 2002268219 CN 1349132	A2 A	20020918	JP 2001-6	9062	20001123 20010312
PRIORITY APPLN. INFO.:		20020515	CN 2001-1 JP 2000-3129	29 A	20011013 20001013
TT 43.01.00 3.0 0.0			JP 2001-6906	2 A	20010312

IT 410100-32-2P

RL: PRP (Properties); SPN (Synthetic preparation); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses) (photosensitive composition for lithog. printing plate containing)

410100-32-2 CAPLUS

CN2-Propenoic acid, 2-methyl-, 2-(2-methoxyethoxy)ethyl ester, polymer with 4-ethenyl-N-(phenylsulfonyl)benzenesulfonamide and methyl 2-propenoate (9CI) (CA INDEX NAME)

CRN 47121-58-4 CMF C14 H13 N O4 S2

CM 2

CRN 45103-58-0 CMF C9 H16 O4

CM 3

CRN 96-33-3 CMF C4 H6 O2